Wordentec; high vacuum and
Thin film coating system
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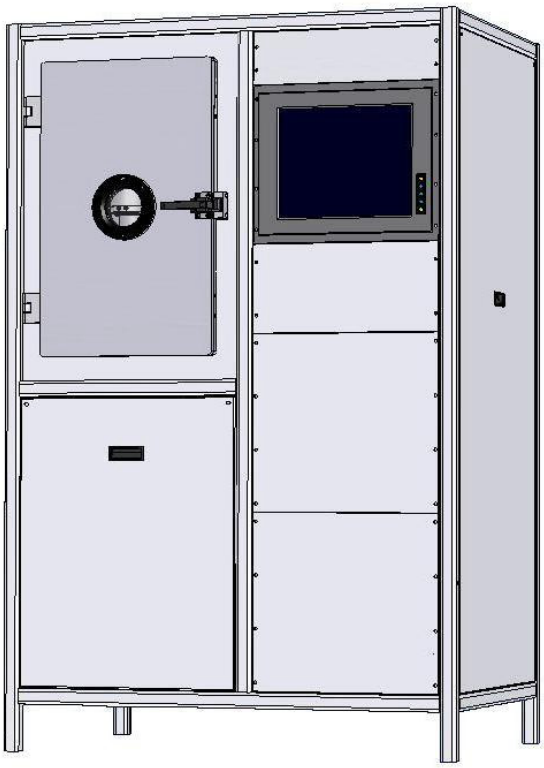
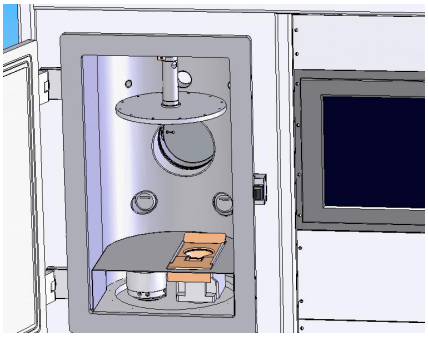
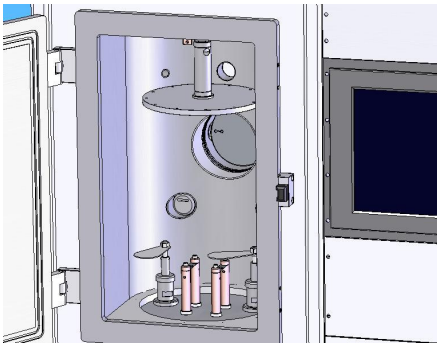
WAVE 360 Laboratory Coater for Optical and Electronic Thin Film r&d.

A front-loading PVD system designed for optical and electronic thin film development. A wide choice of accessories allow the *WAVE* 360 to be configured for a range of PVD processes including electron beam evaporation, sputtering and thermal evaporation. The *WAVE* 360 is a highly capable successor to the now obsolete Edwards 306.

Manufactured in the UK.







1. Chamber:

D shape, non-magnetic stainless steel 304L with hinged aluminium door. Viton sealed.
Internal dimensions 360 x 360 x 650 mm
Volume 70 lt
Circular chamber viewport
Spare KF accessory ports

2. Framework:

Polyester powder coated rigid steel framework (1200 w 800 d 1800h) with 40u, 19" rack detail to enable mounting of instruments and power supplies.

3. Pumps:

Turbomolecular high vacuum pump with rotary vane backing pump
(cryogenic and diffusion pump options available)

4. Gauges:

Active pirani / penning gauge

5. Automation:

Auto pump station control.

6. Safety:

Process items safety interlocked with vacuum and chamber door.
Controls and equipment will be constructed to fully comply with all the Essential Health and Safety Requirements of the Machinery Directive 98/37/EEC as amended, and EMC Directive 89/336/EEC. The equipment will be CE marked.

7. Shields:

One set of stainless steel shields supplied.

8. Services required:

Power: 3 kVA (typical, accessory dependent) 1 phase 220 – 240 VAC 50 Hz, option 400 VAC 3 phase

Accessories, options and upgrades:

9. Deposition monitor:

Inficon quartz crystal film thickness monitor with water cooled crystal holder

10. Evaporation sources:

2 no high current resistance evaporation sources

11. Shutter:

Pneumatic source shutter controlled by deposition monitor.

12. Substrate carrier:

Rotating substrate carrier, motor drive with variable speed. 150 mm diameter .
Domes and planetary systems also available.

13. Heating:

Quartz infrared heating with digital PID temperature controller, solid state thyristor drive and power isolating transformer.

14. Glow discharge:

High voltage power supply, feedthrough and gas inlet control for glow discharge cleaning.

15. Sputtering:

Chamber configuration allows upgrade to sputter coater by baseplate substitution. Single, 3 x 75mm or 4 x 50mm target configuration are possible.

16. Electron beam evaporation:

Chamber configuration allows upgrade to ebeam evaporator. Multi pocket evaporator (1, 4 or 6 materials) up to 10KV 3 kW solid state generator and digital scan controller.